

ABSTRACT

A photosensitive composition remover used for removal of an uncured photosensitive composition, which
5 remover comprises 1 to 80 percent by mass of at least one
type of aromatic hydrocarbon having 9 carbon atoms or
more within the molecule. The photosensitive composition
remover further comprises an aprotic polar solvent and/or
another solvent other than aprotic polar solvents. The
10 photosensitive composition remover is effective for
removal of an uncured photosensitive composition film
deposited at the periphery, edges, or back of a substrate
or removal of an uncured photosensitive composition
deposited at the surface of system members or equipment
15 in a process for forming a photosensitive composition
film on a glass substrate, a semiconductor wafer, or the
like. It is preferably used for removal of a
photosensitive composition containing a pigment in a
process for forming a photosensitive composition film on
20 a substrate in the process of production of a liquid
crystal or an organic EL display.